

FIG. 1

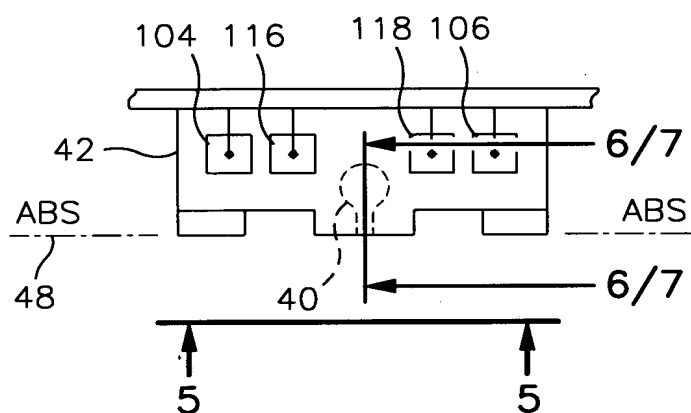


FIG. 2

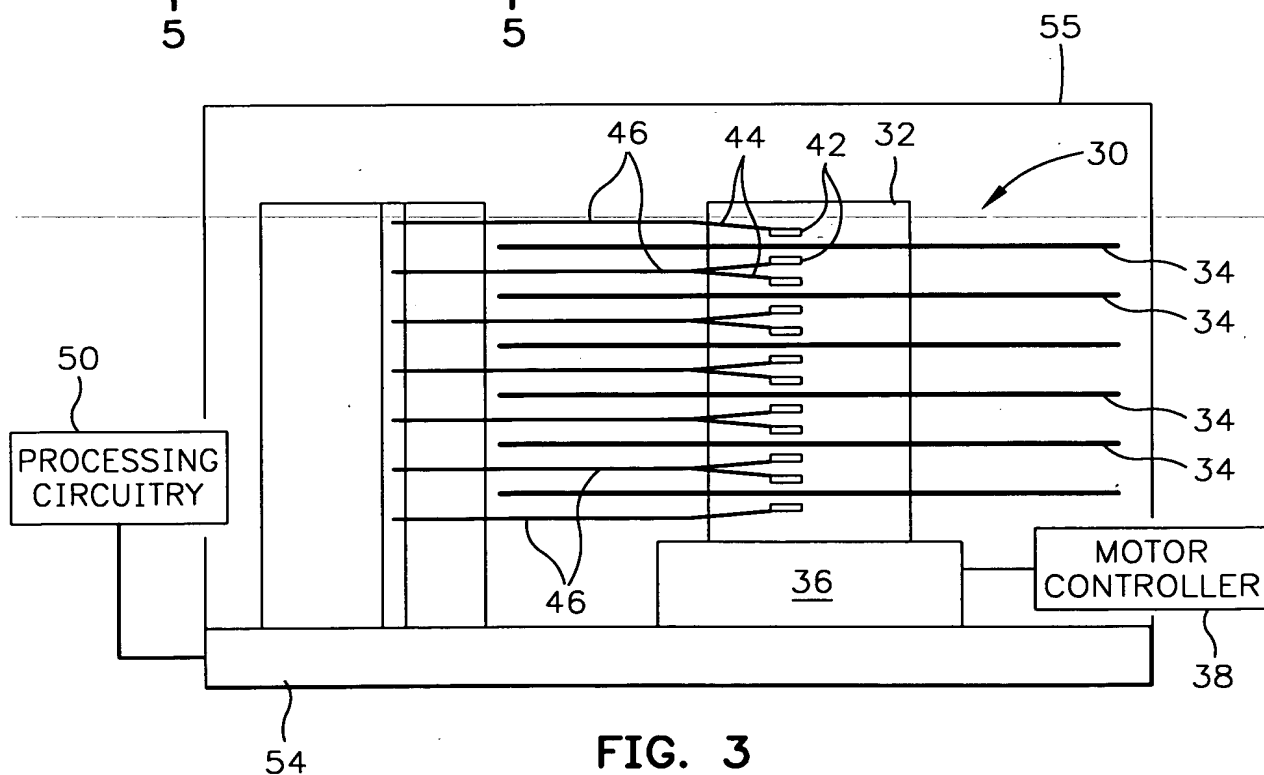


FIG. 3

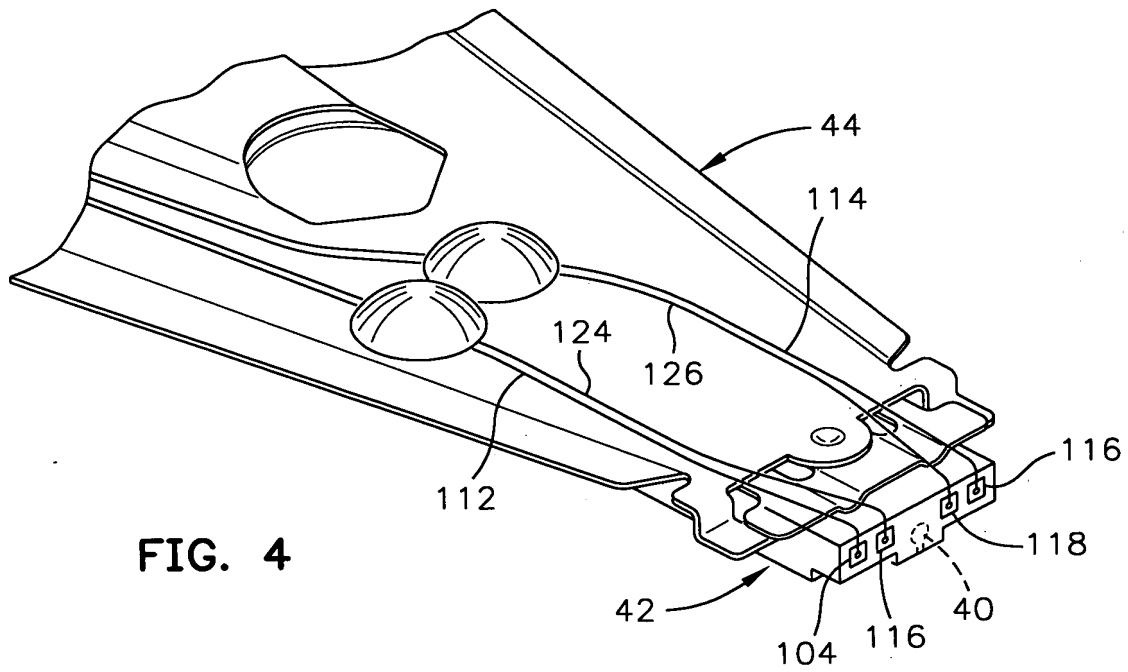


FIG. 4

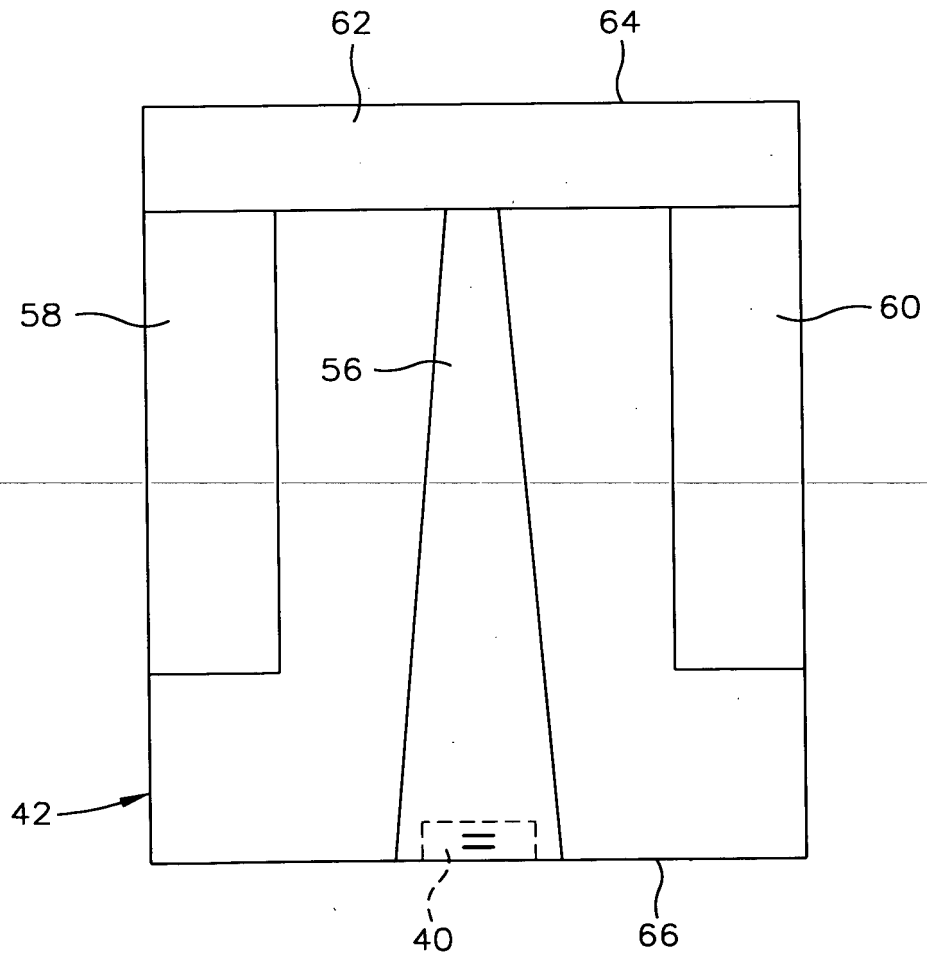


FIG. 5

FIG. 6

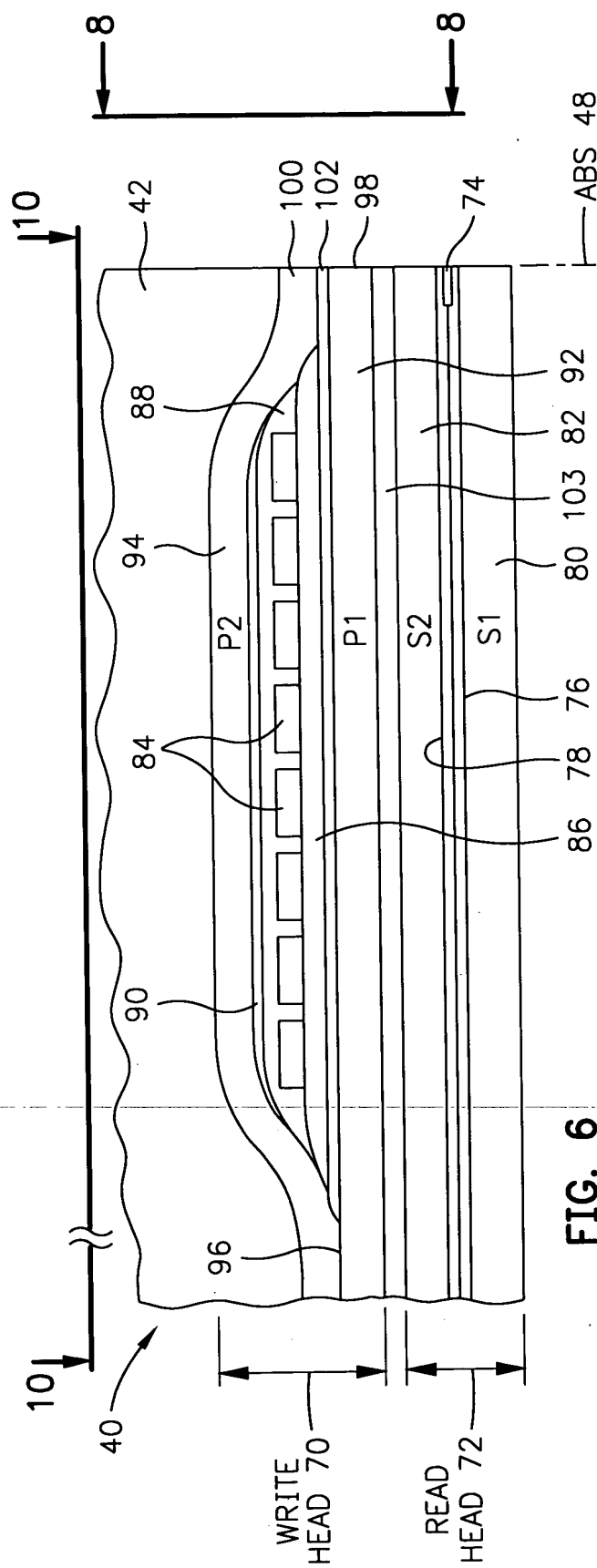
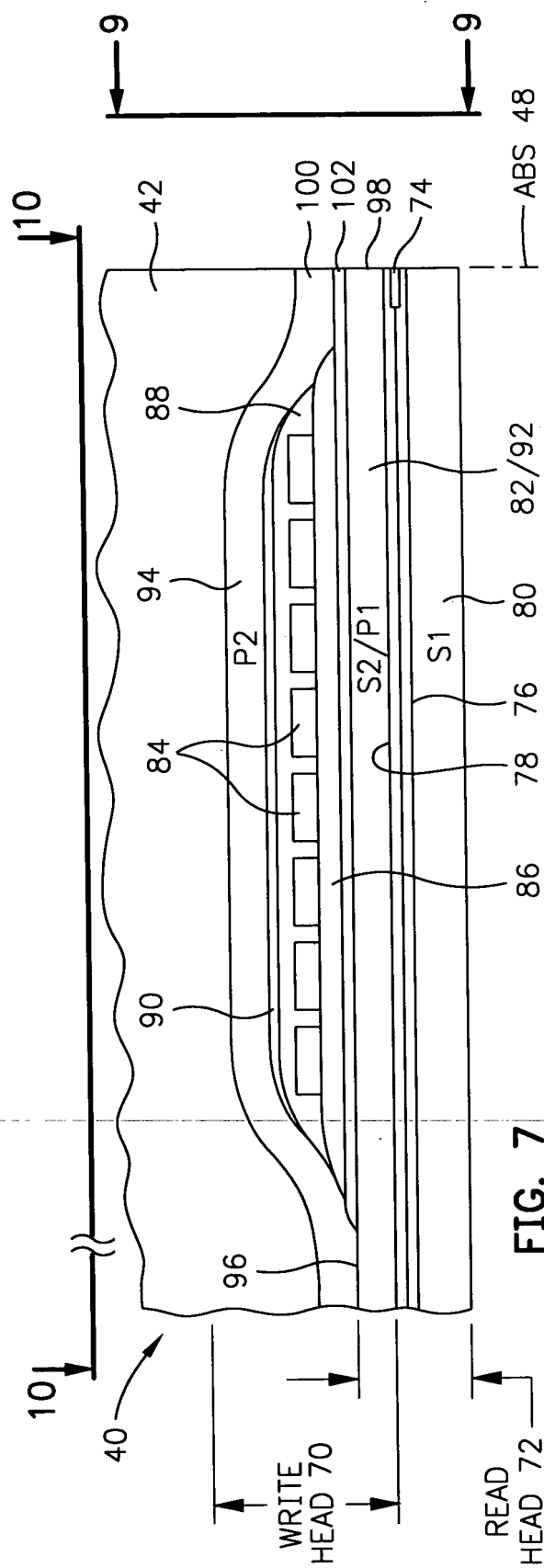


FIG. 7



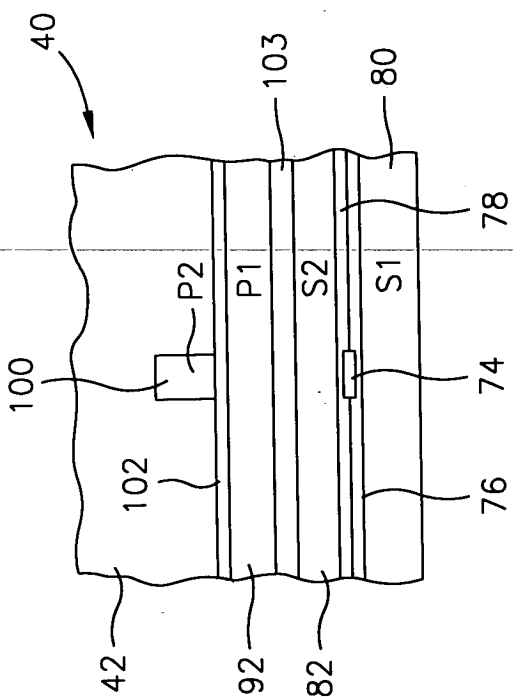


FIG. 8

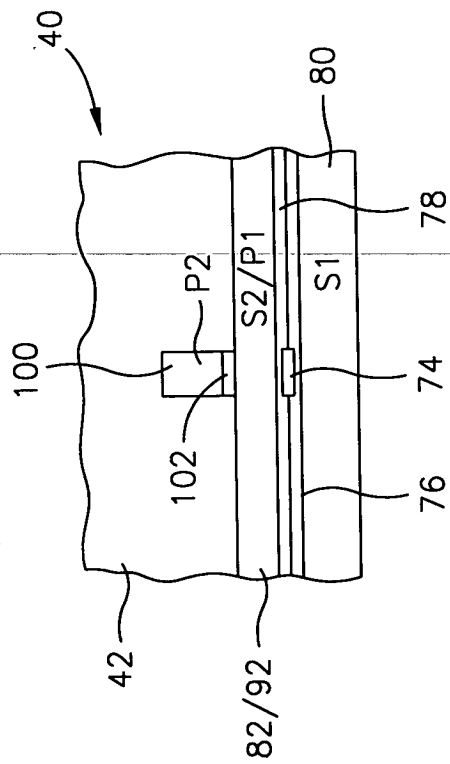


FIG. 9

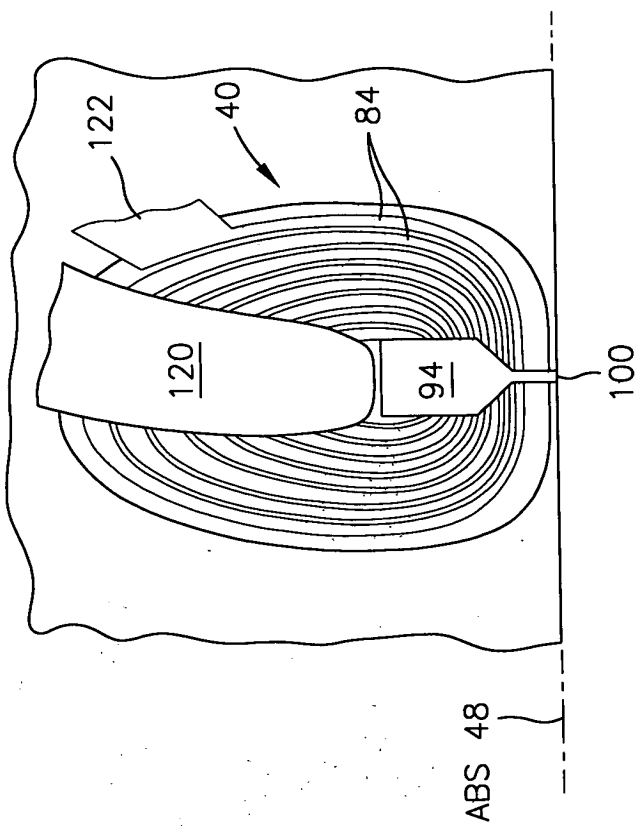


FIG. 10

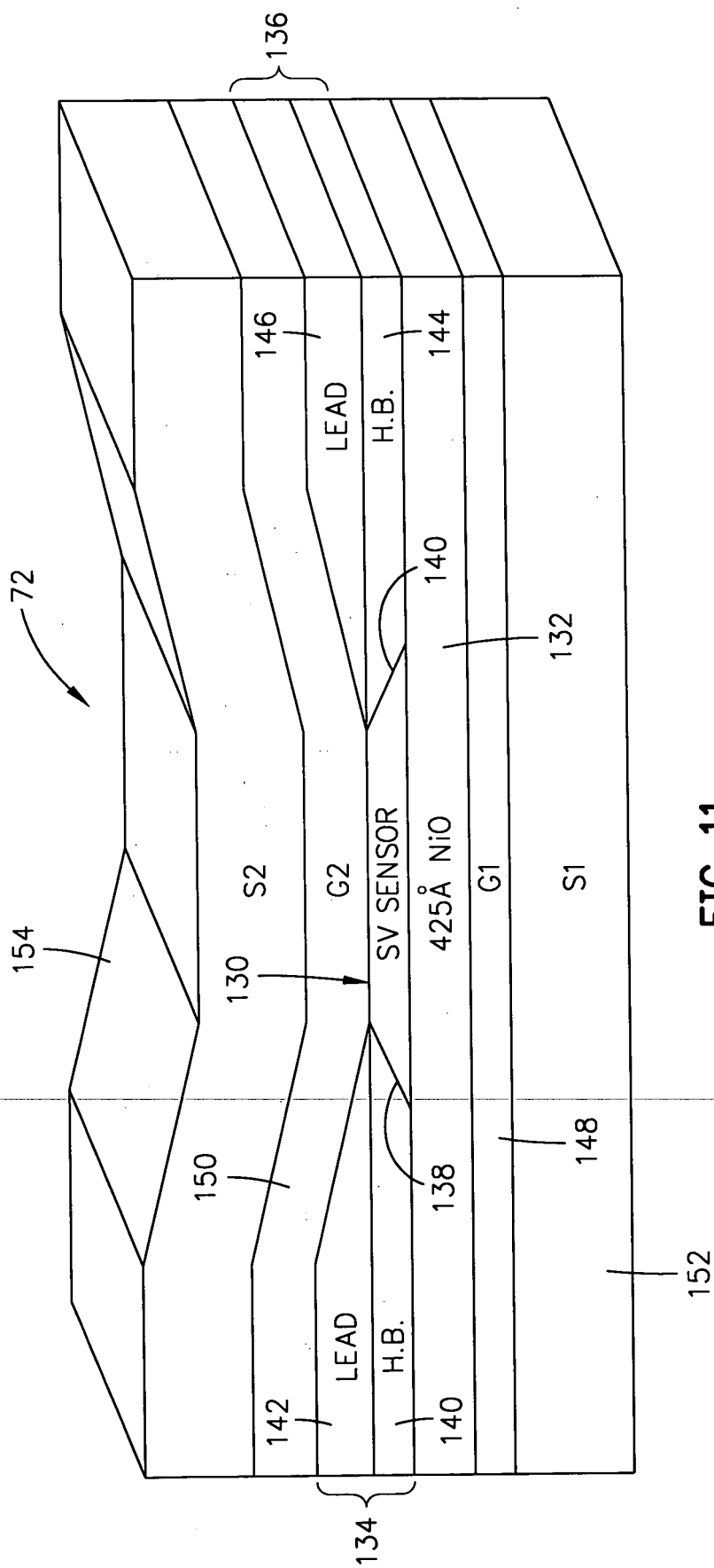


FIG. 11
(ABS)

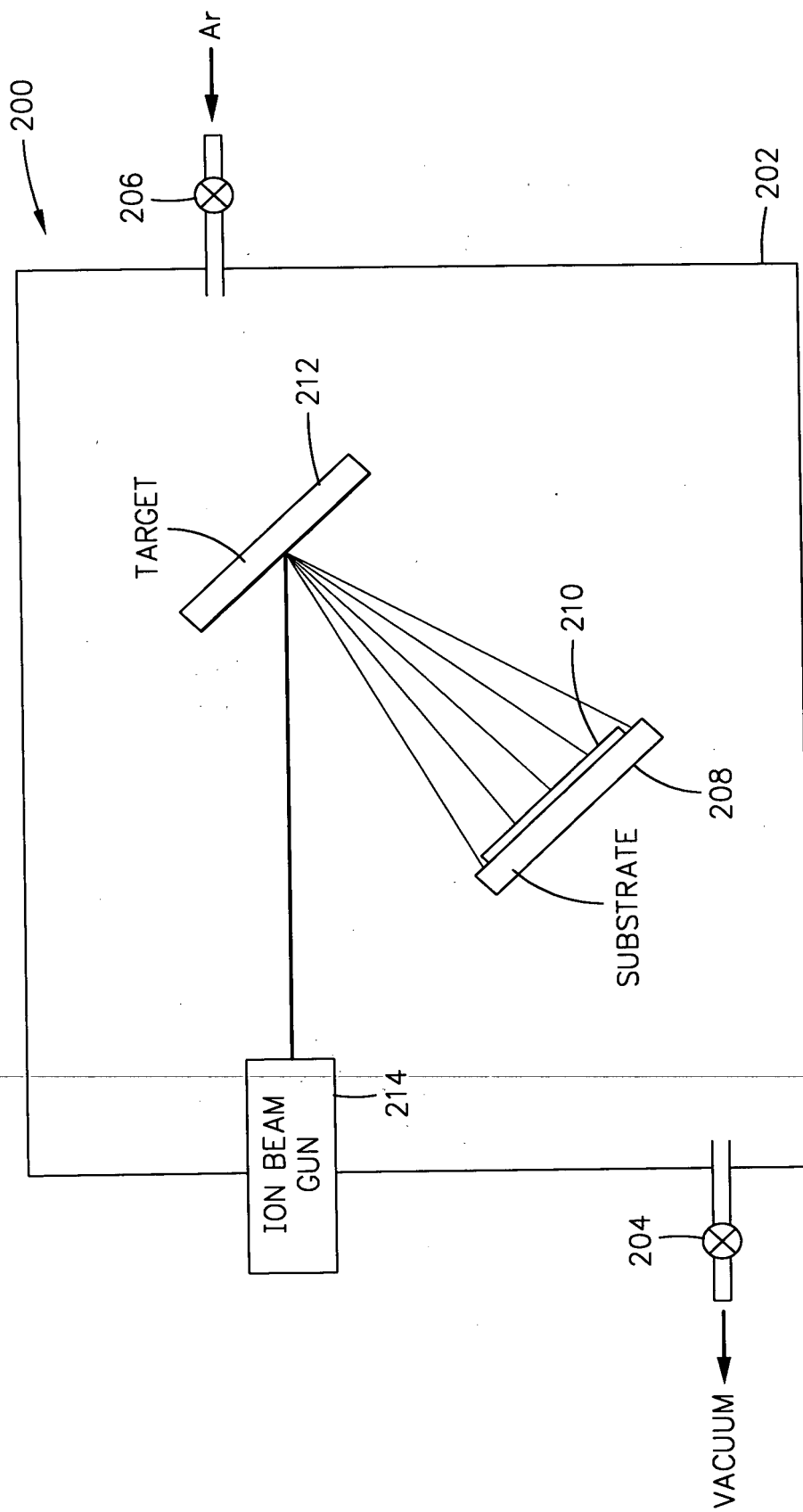


FIG. 12
(PRIOR ART)

FIG. 13 is a schematic diagram of a sputtering system 250. The system includes an ion beam gun 214, a target 212, a substrate 208, and a chamber 202. The ion beam gun 214 is connected to the target 212. The target 212 is positioned above the substrate 208. The substrate 208 is mounted on a pedestal 210. The chamber 202 is evacuated by a vacuum pump 204. An argon gas inlet 206 is also shown.

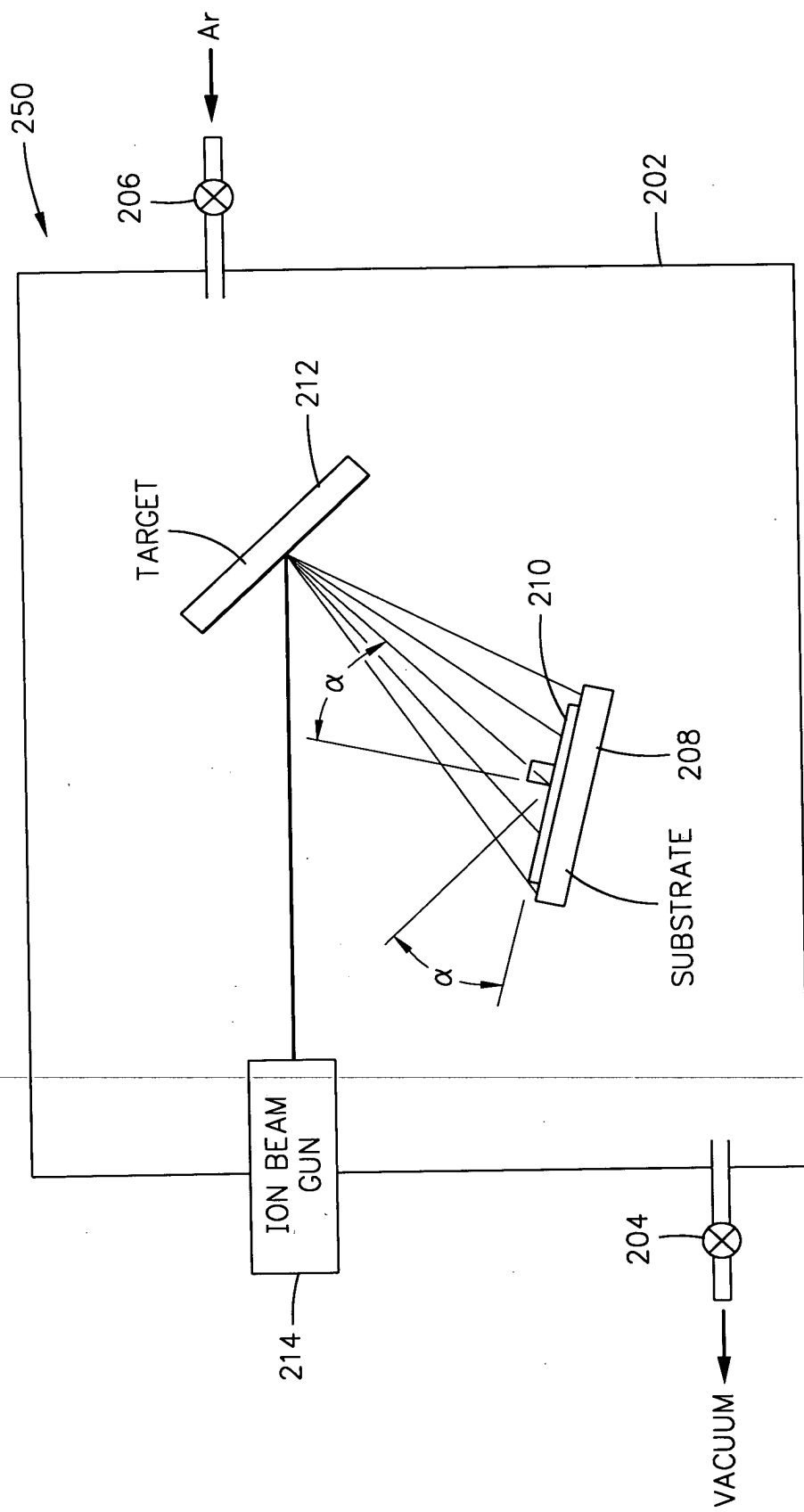
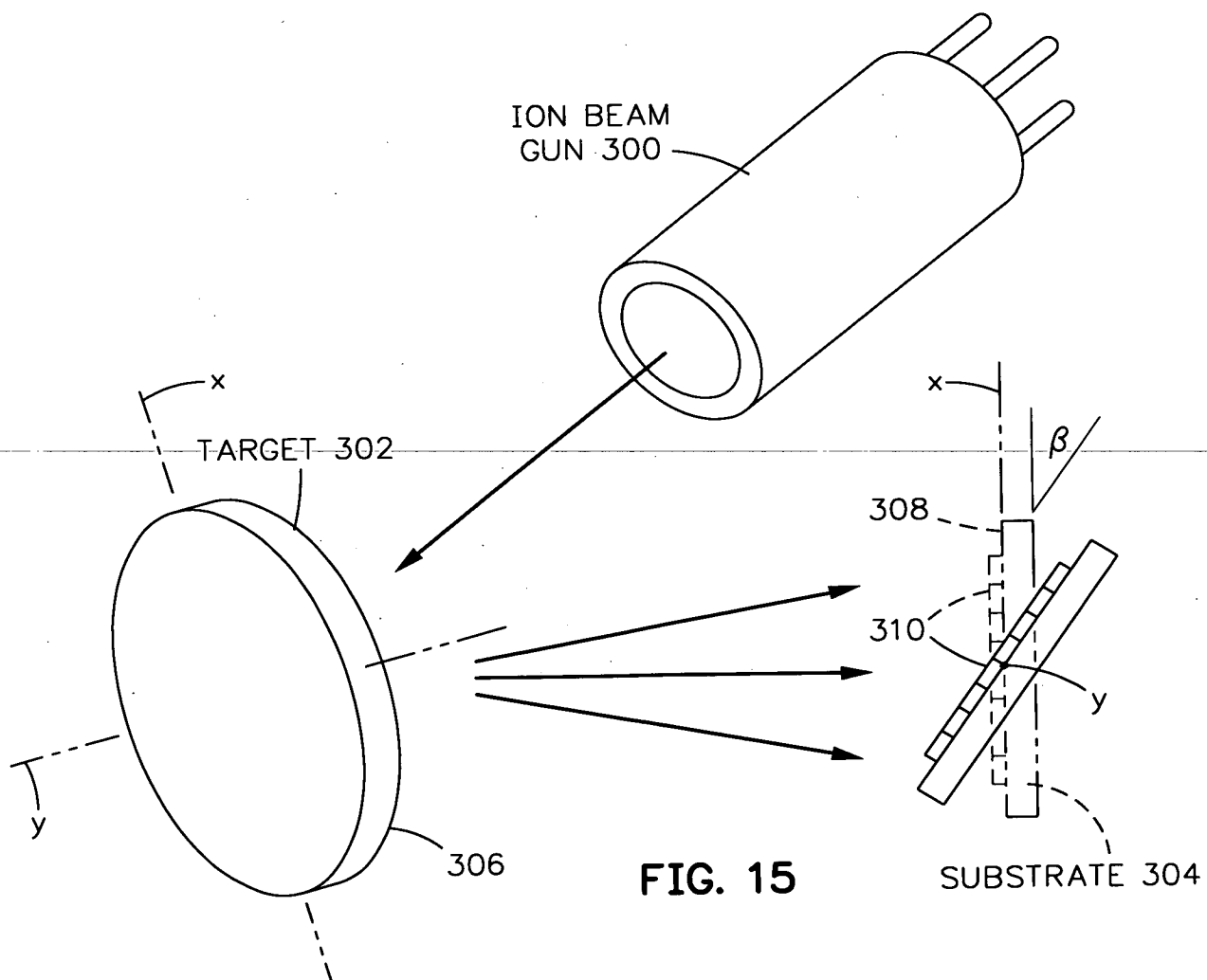
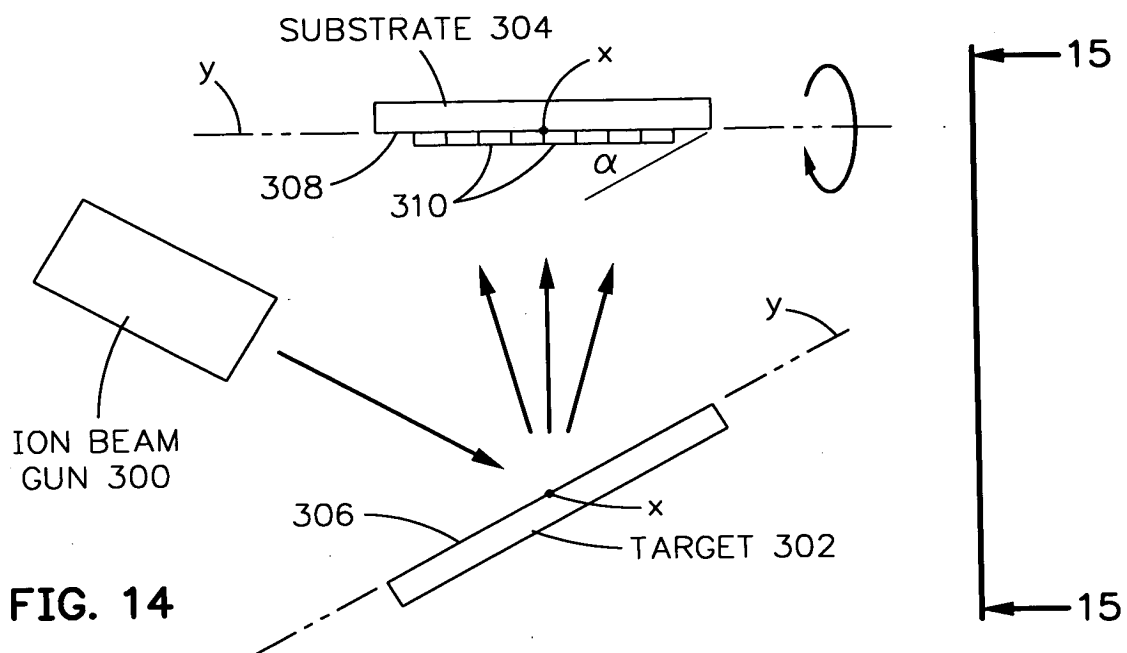


FIG. 13



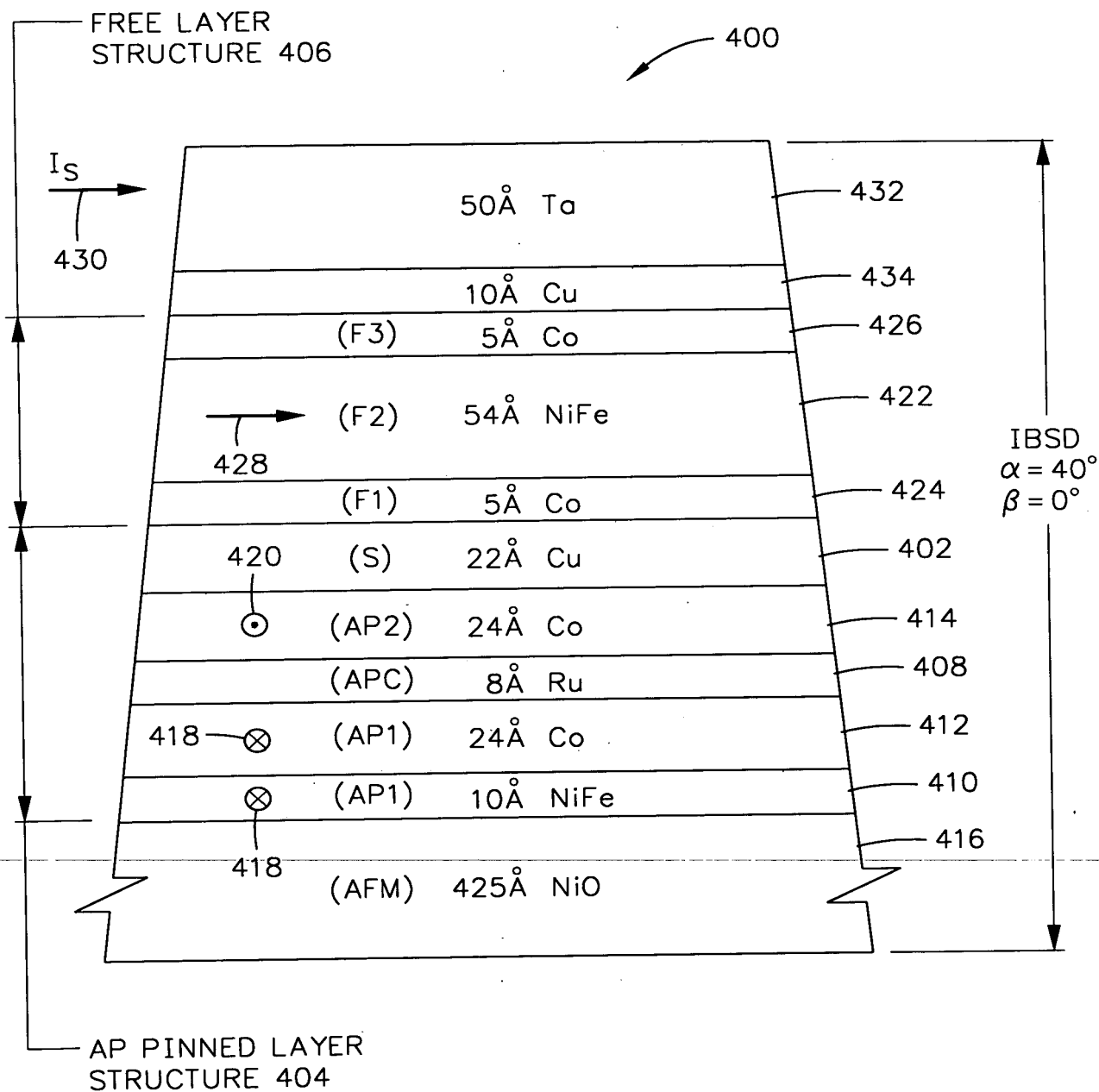


FIG. 16

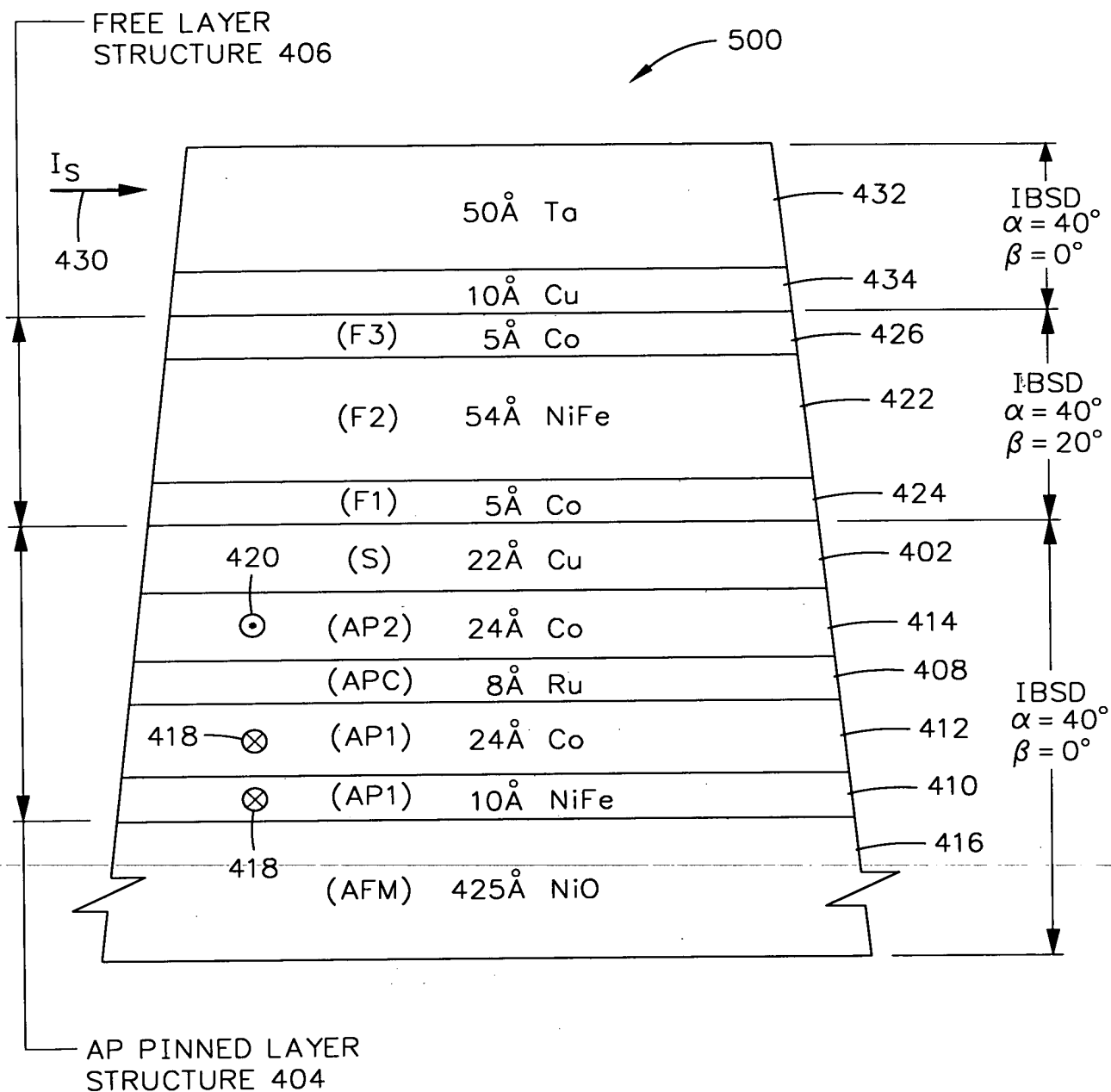


FIG. 17

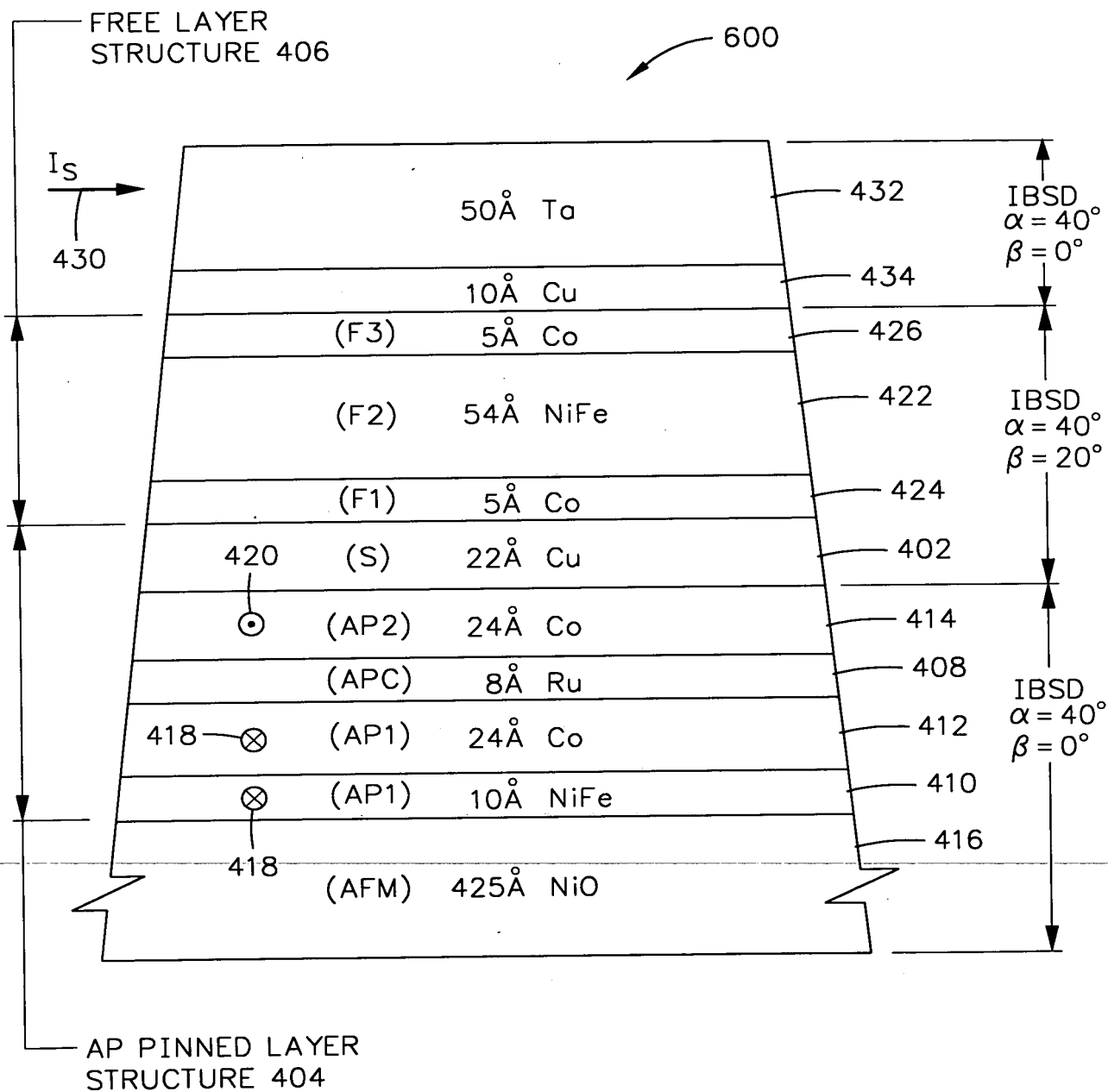


FIG. 18

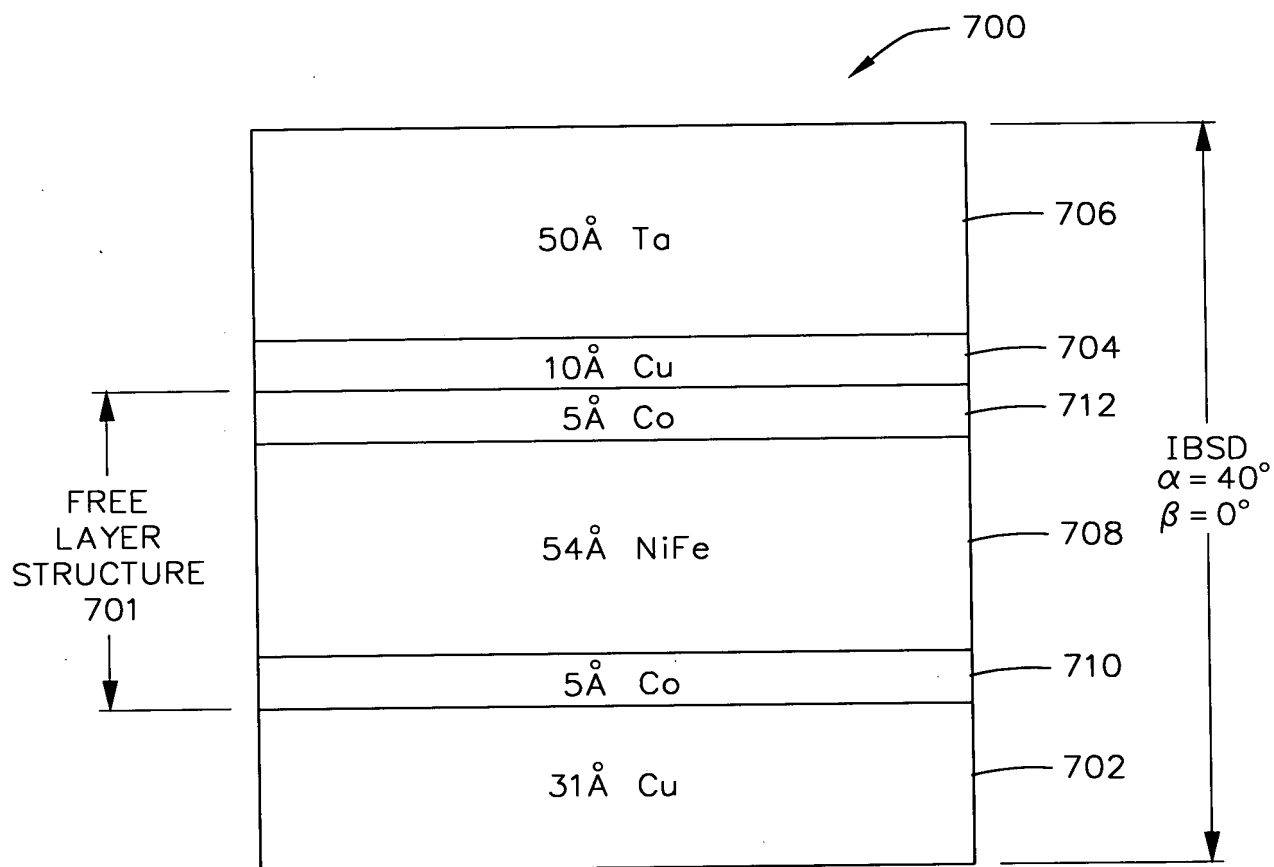


FIG. 19

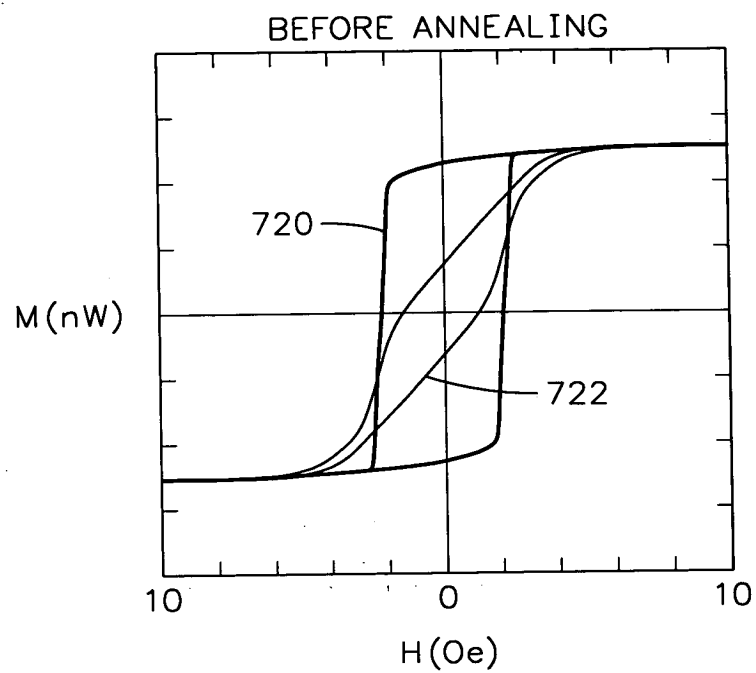


FIG. 20A

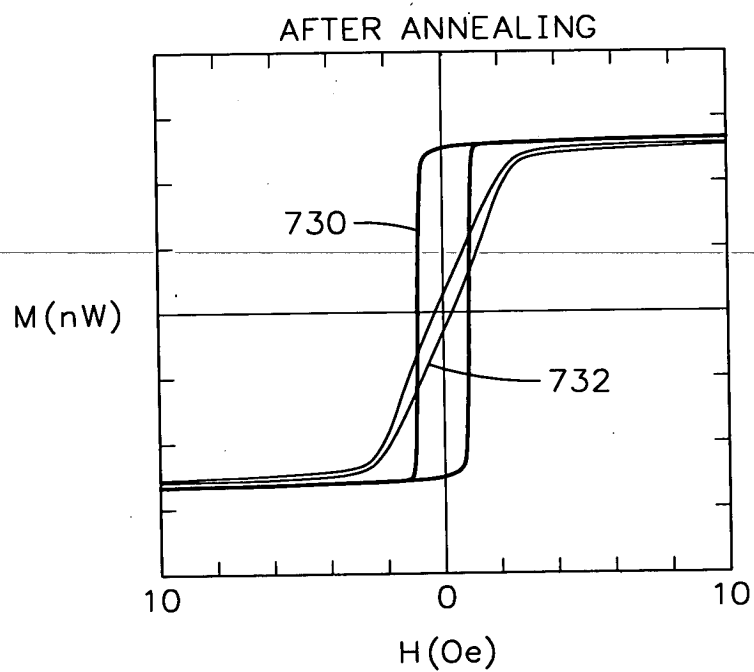


FIG. 20B

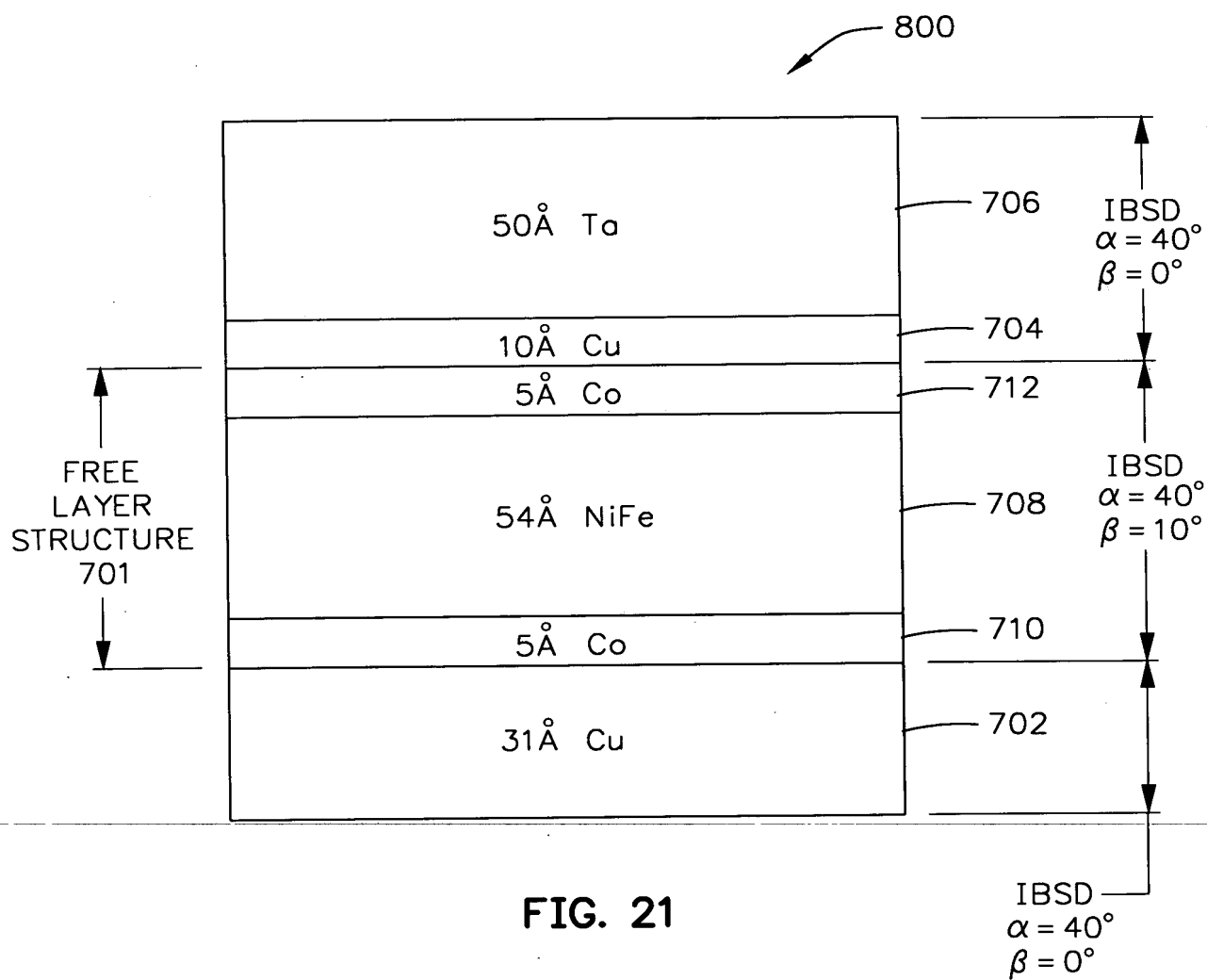


FIG. 21

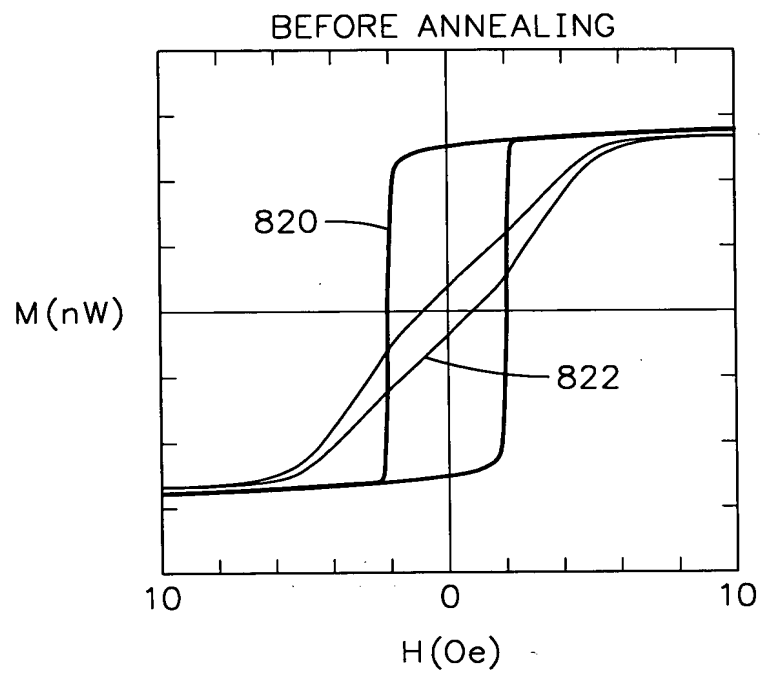


FIG. 22A

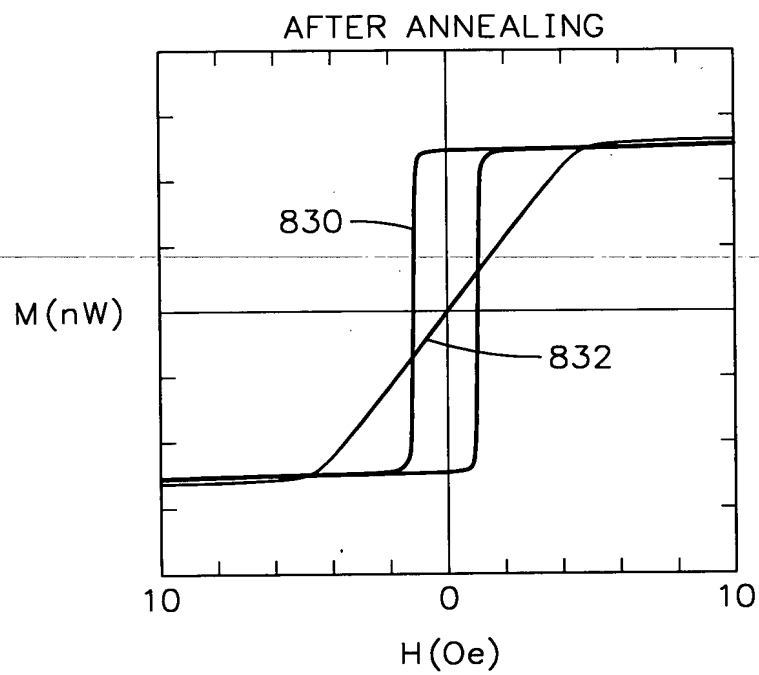


FIG. 22B

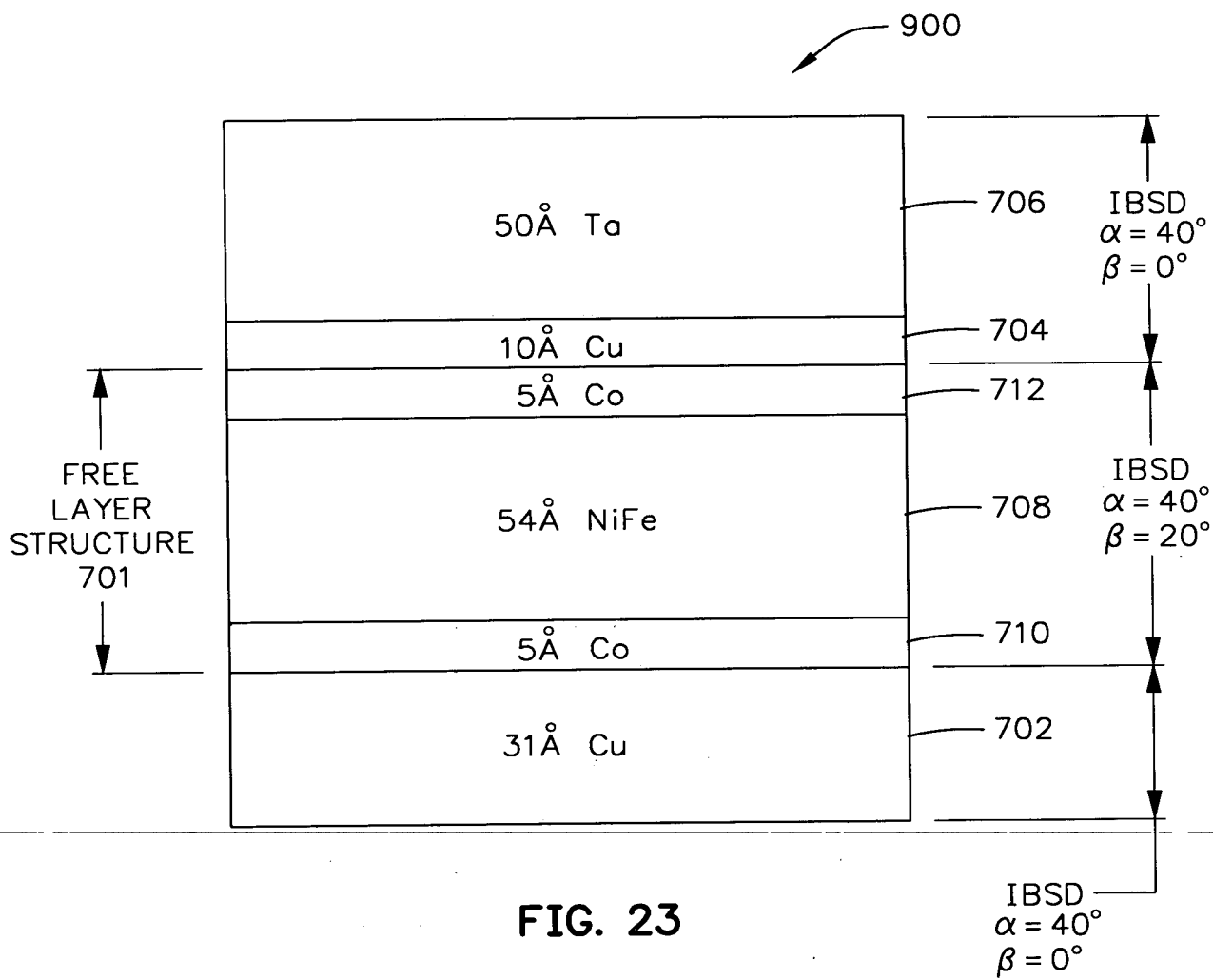


FIG. 23

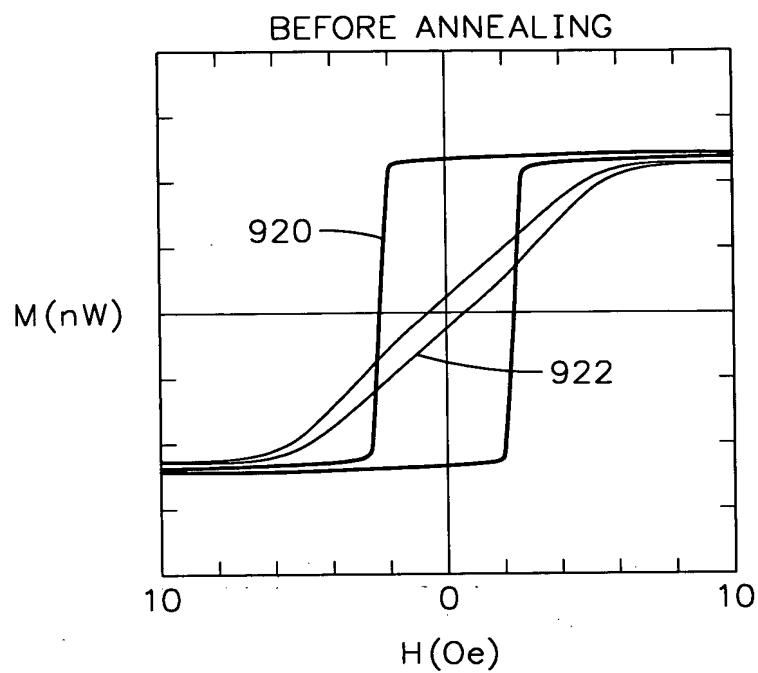


FIG. 24A

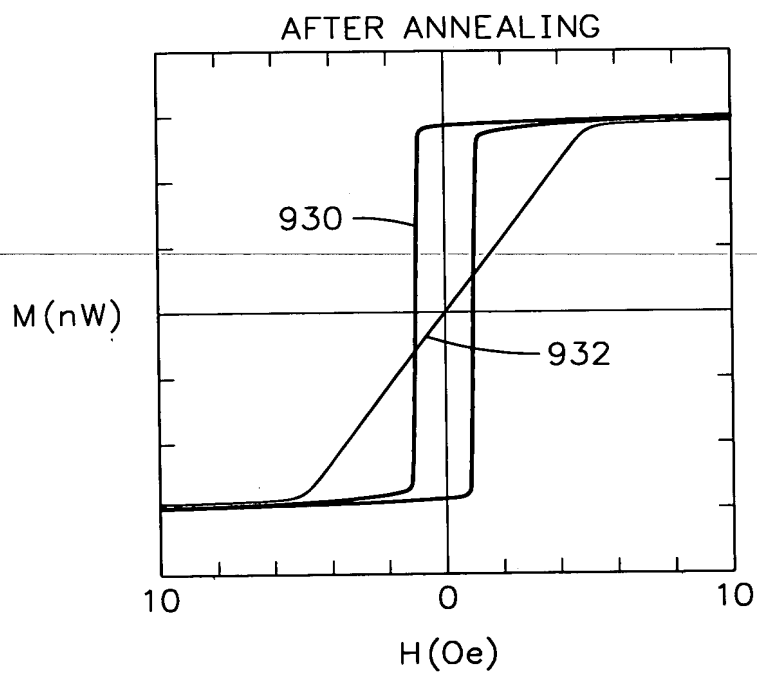


FIG. 24B

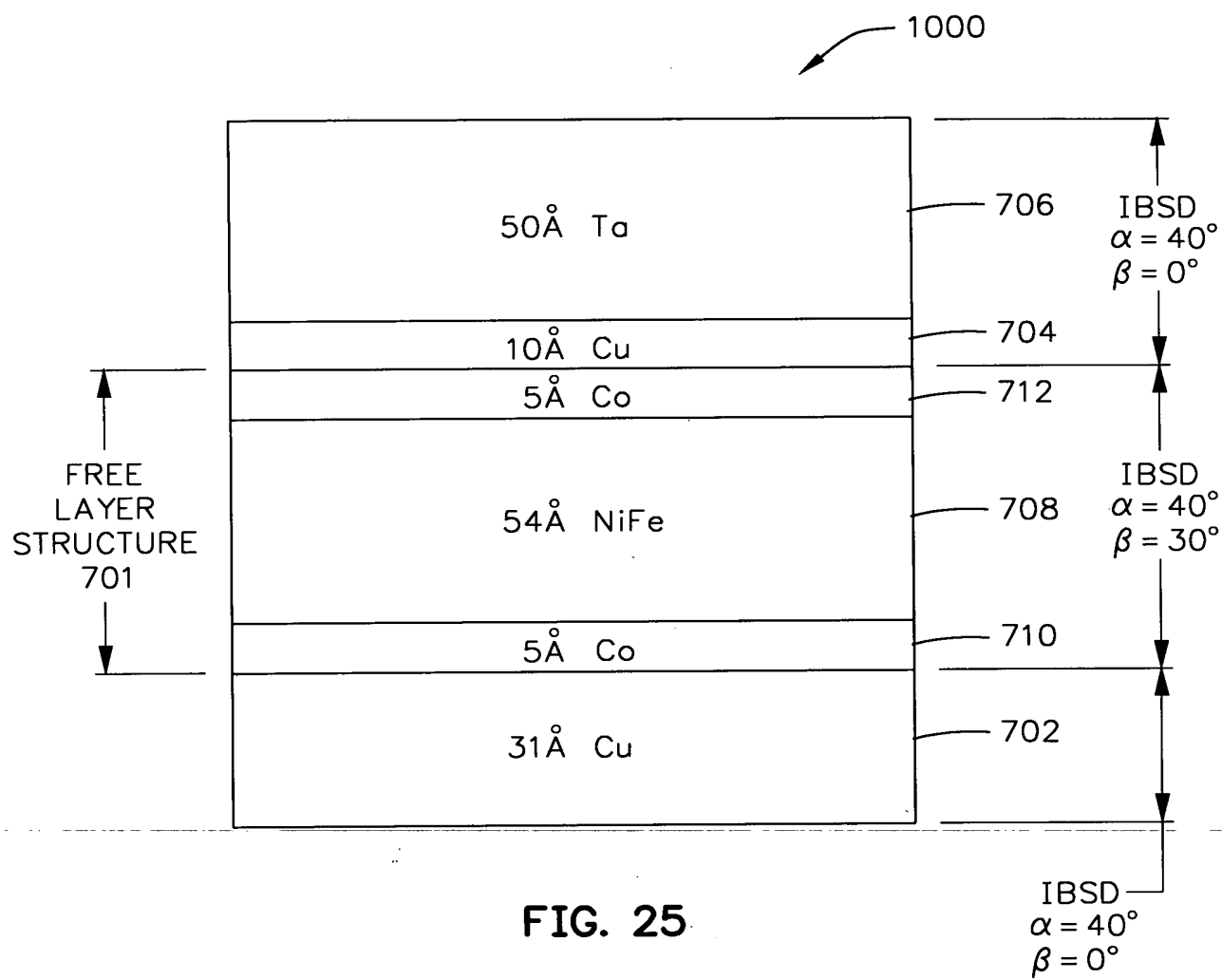


FIG. 25

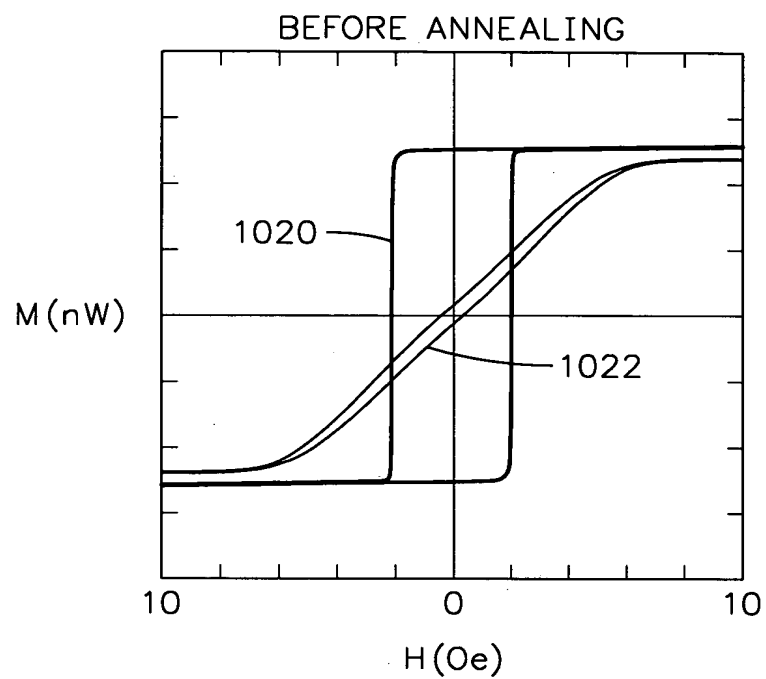


FIG. 26A

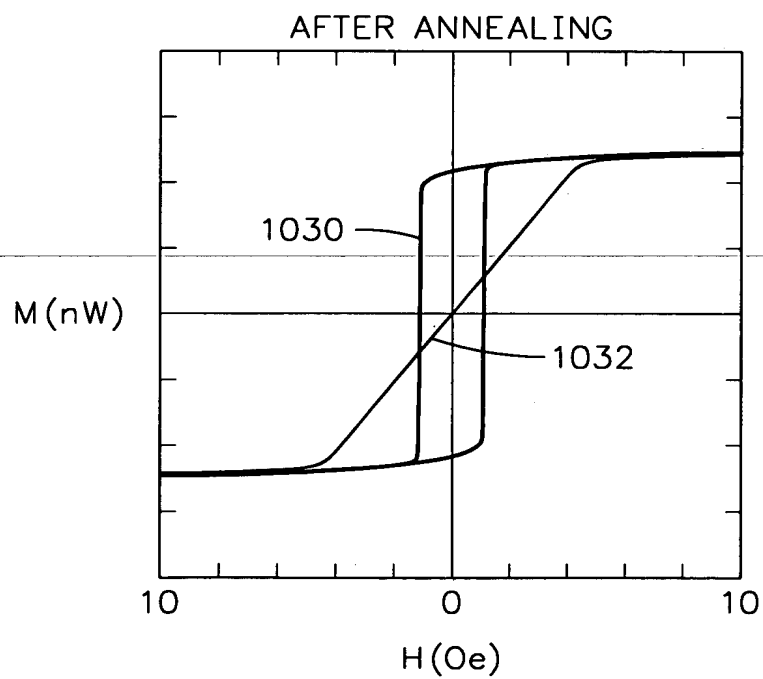


FIG. 26B

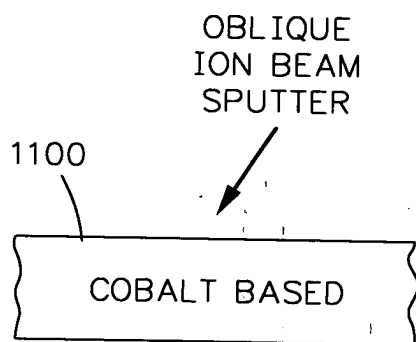


FIG. 27A

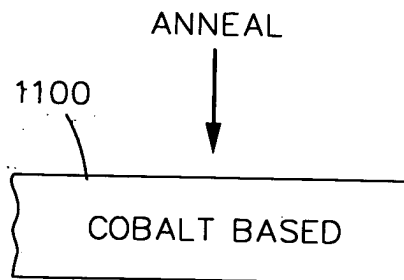


FIG. 27B

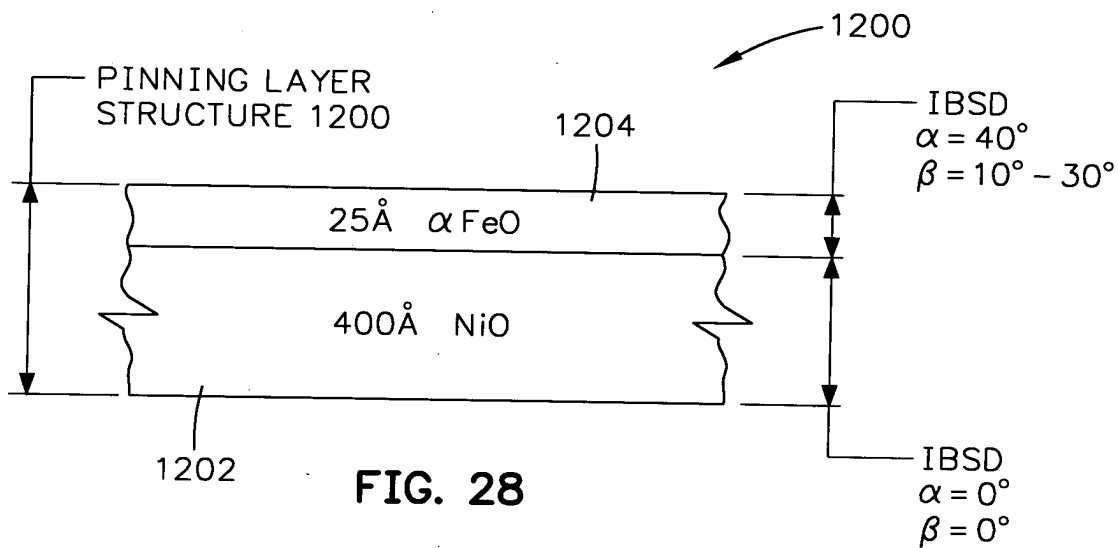


FIG. 28

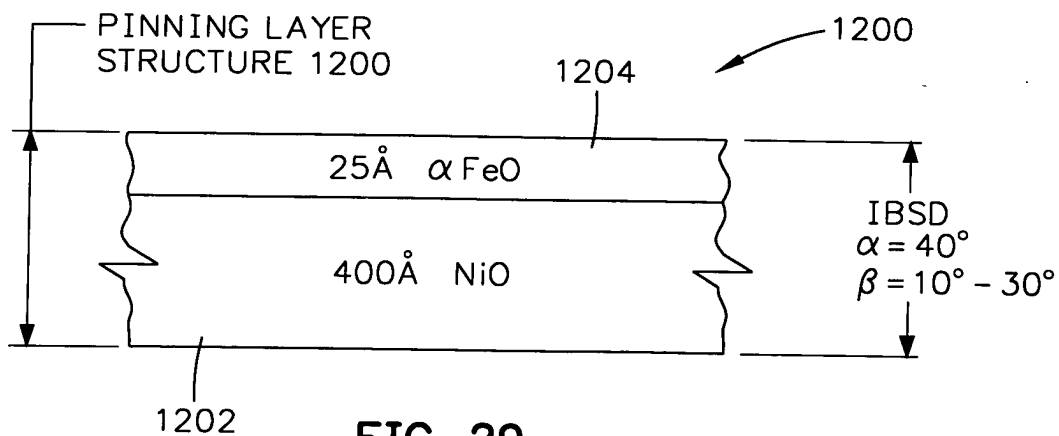


FIG. 29